

ABSTRACT OF THE DISCLOSURE

A method of fabricating an array substrate for use in an LCD device which can be used in a four-, five- or six-mask process includes simultaneously etching layers formed over gate and data pads. When performing a photolithography process, photoresist remains over the data pad and acts as an etch stopper. And thus, while etching the layers over the gate pad, the layers over the data pad are etched without any damage to the data pad and without overetching the data pad. Therefore, defects caused by the resistance between the data pad and the data pad electrode do not occur, and pixel defects in the LCD device are prevented. Moreover, the manufacturing yield increases when this method is used.